

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments	Error Definition
1	BRS	L1	1	etch\$3 and (damascene or "dual damascene" or interconnect\$3) and wir\$3 and "bi layer mask"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWE NT; IBM_T B	2005/09/29 16:36		
2	BRS	L2	127	etch\$3 and (damascene or "dual damascene" or interconnect\$3) and wir\$3 and (((imag\$3 and silicon) adj3 (mask or photoresist or resist)) or "bi layer mask")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWE NT; IBM_T B	2005/09/29 19:31		
3	BRS	L3	67	2 and @pd<="20030929"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWE NT; IBM_T B	2005/09/29 19:32		
4	BRS	L4	125	YE-YAN.in.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWE NT; IBM_T B	2005/09/29 19:27		

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments	Error Definition
5	BRS	L5	22262	ZHAO- XIAOYE.in.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWE NT; IBM_TD B	2005/09/29 19:28		
6	BRS	L6	20	ZHAO-XIAOYE.in.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWE NT; IBM_TD B	2005/09/29 19:30		
7	BRS	L7	14	DU-HONG.in.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWE NT; IBM_TD B	2005/09/29 19:30		
8	BRS	L8	2	7 not "20"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWE NT; IBM_TD B	2005/09/29 19:30		

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments	Error Definition
9	BRS	L9	463	etch\$3 and (damascene or "dual damascene" or interconnect\$3) and wir\$3 and (((imag\$3 and silicon) adj3 (mask or photoresist or resist)) or "bi layer")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWE NT; IBM_TDB	2005/09/29 19:31		
10	BRS	L10	181	9 and @pd<="20030929"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWE NT; IBM_TDB	2005/09/29 19:32		
11	BRS	L11	114	10 not 3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWE NT; IBM_TDB	2005/09/29 19:32		
12	BRS	L12	1	"5882996".PN.	USPAT; USOCR	2005/09/29 19:46		